

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1752YXC

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

\* \* \* \* \* Welcome to STN International \* \* \* \* \*

NEWS	1		Web Page URLs for STN Seminar Schedule - N. America
NEWS	2		"Ask CAS" for self-help around the clock
NEWS	3	May 12	EXTEND option available in structure searching
NEWS	4	May 12	Polymer links for the POLYLINK command completed in REGISTRY
NEWS	5	May 27	New UPM (Update Code Maximum) field for more efficient patent SDIs in CPlus
NEWS	6	May 27	CPlus super roles and document types searchable in REGISTRY
NEWS	7	Jun 28	Additional enzyme-catalyzed reactions added to CASREACT
NEWS	8	Jun 28	ANTE, AQUALINE, BIOENG, CIVILENG, ENVIROENG, MECHENG, and WATER from CSA now available on STN(R)
NEWS	9	Jul 12	BEILSTEIN enhanced with new display and select options, resulting in a closer connection to BABS
NEWS	10	Jul 30	BEILSTEIN on STN workshop to be held August 24 in conjunction with the 228th ACS National Meeting
NEWS	11	AUG 02	IFIPAT/IFIUDB/IFICDB reloaded with new search and display fields
NEWS	12	AUG 02	CPlus and CA patent records enhanced with European and Japan Patent Office Classifications
NEWS	13	AUG 02	STN User Update to be held August 22 in conjunction with the 228th ACS National Meeting
NEWS	14	AUG 02	The Analysis Edition of STN Express with Discover! (Version 7.01 for Windows) now available
NEWS	15	AUG 04	Pricing for the Save Answers for SciFinder Wizard within STN Express with Discover! will change September 1, 2004
NEWS	16	AUG 27	BIOCOMMERCE: Changes and enhancements to content coverage
NEWS	17	AUG 27	BIOTECHABS/BIOTECHDS: Two new display fields added for legal status data from INPADOC
NEWS	18	SEP 01	INPADOC: New family current-awareness alert (SDI) available
NEWS	19	SEP 01	New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover!
NEWS	20	SEP 01	New display format, HITSTR, available in WPIDS/WPINDEX/WPIX
NEWS	21	SEP 14	STN Patent Forum to be held October 13, 2004, in Iselin, NJ
NEWS EXPRESS		JULY 30	CURRENT WINDOWS VERSION IS V7.01, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 11 AUGUST 2004
NEWS HOURS			STN Operating Hours Plus Help Desk Availability
NEWS INTER			General Internet Information
NEWS LOGIN			Welcome Banner and News Items
NEWS PHONE			Direct Dial and Telecommunication Network Access to STN
NEWS WWW			CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

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\* \* \* \* \* STN Columbus \* \* \* \* \*

FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004

=> file reg

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.21

0.21

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5

DICTIONARY FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5

TSCA INFORMATION NOW CURRENT THROUGH MAY 21, 2004

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:

<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> ....Testing the current file.... screen

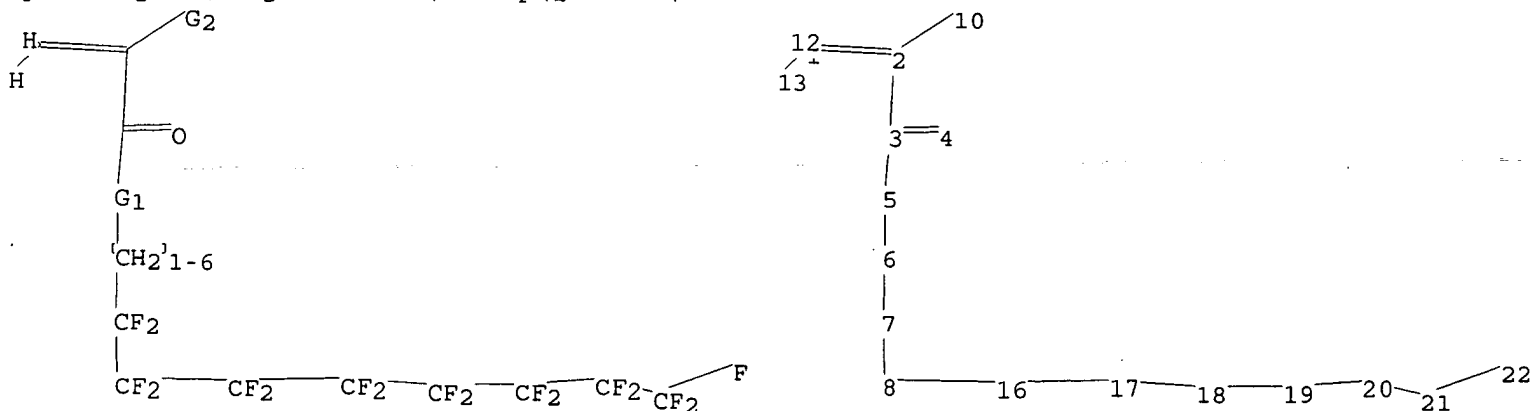
ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L1 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10642576-3.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18 19 20 21 22

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21 21-22

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21 21-22

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS  
13:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS 21:CLASS 22:CLASS

L2 STRUCTURE UPLOADED

=> que L2 AND L1

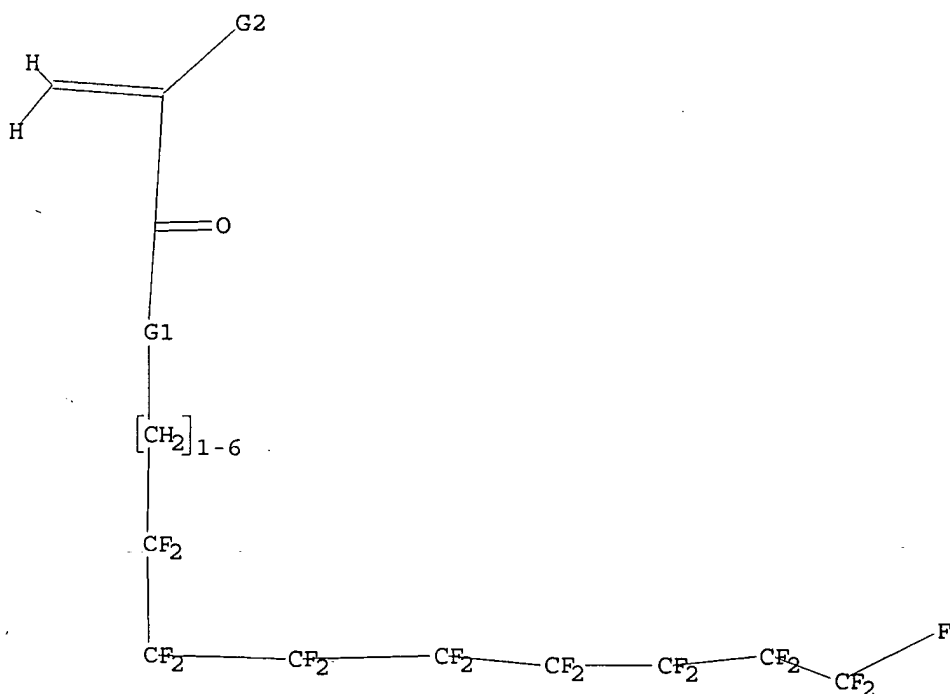
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 970 AND 2067

L2 STR



G1 O,S,N

G2 CH<sub>2</sub>,H

Structure attributes must be viewed using STN Express query preparation.

L3 QUE ABB=ON PLU=ON L2 AND L1

=> s l3 sss sam

SAMPLE SEARCH INITIATED 20:40:00 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 350 TO ITERATE

100.0% PROCESSED 350 ITERATIONS

50 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
 BATCH \*\*COMPLETE\*\*  
 PROJECTED ITERATIONS: 5878 TO 8122  
 PROJECTED ANSWERS: 2990 TO 4648

L4 50 SEA SSS SAM L2 AND L1

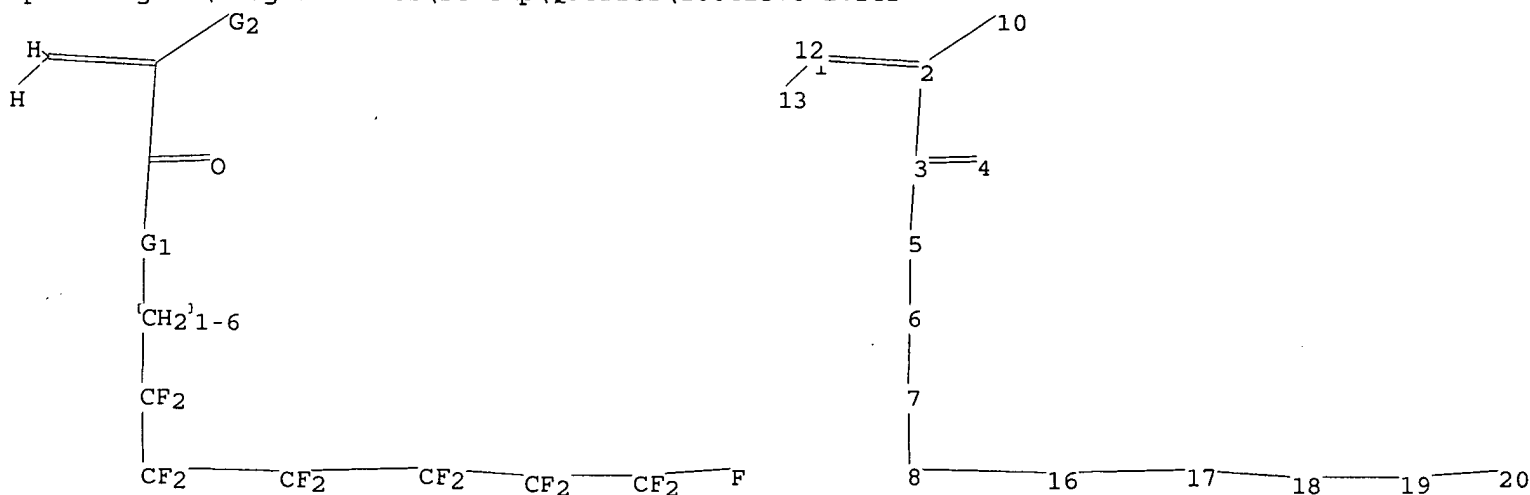
=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L5 SCREEN CREATED

=>  
 Uploading C:\Program Files\Stnexp\Queries\10642576-2.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18 19 20

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18 18-19 19-20

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18 18-19 19-20

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS  
 13:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS

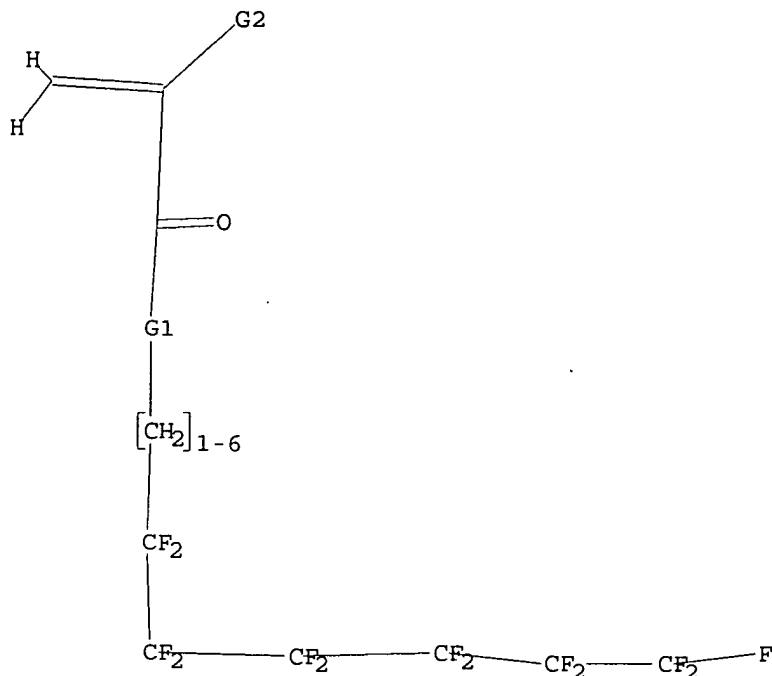
L6 STRUCTURE UPLOADED

=> que L6 AND L5

L7 QUE L6 AND L5

=> d

L7 HAS NO ANSWERS  
 L5 SCR 970 AND 2067  
 L6 STR



G1 O,S,N  
 G2 CH2,H

Structure attributes must be viewed using STN Express query preparation.

L7 QUE ABB=ON PLU=ON L6 AND L5

=> s l7 sss sam

SAMPLE SEARCH INITIATED 20:40:33 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 415 TO ITERATE

100.0% PROCESSED 415 ITERATIONS  
 SEARCH TIME: 00.00.01

39 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
 BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 7078 TO 9522  
 PROJECTED ANSWERS: 406 TO 1154

L8 39 SEA SSS SAM L6 AND L5

=> ....Testing the current file.... screen

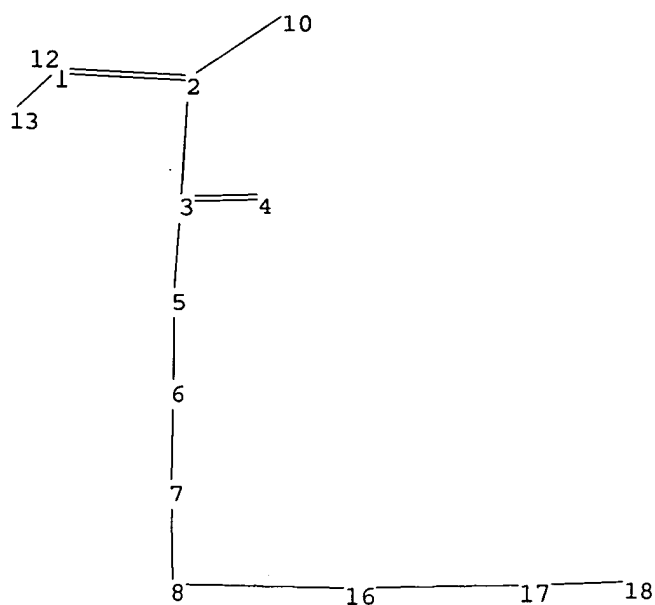
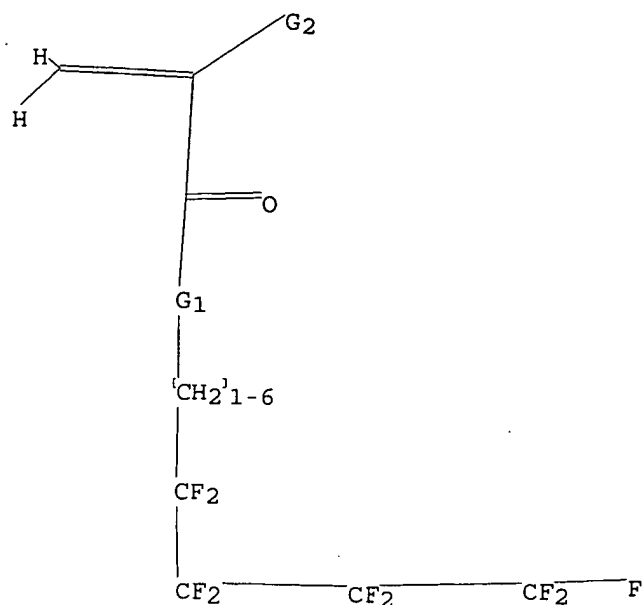
ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L9 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10642576-1.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS

13:CLASS 16:CLASS 17:CLASS 18:CLASS

L10 STRUCTURE UPLOADED

=> que L10 AND L9

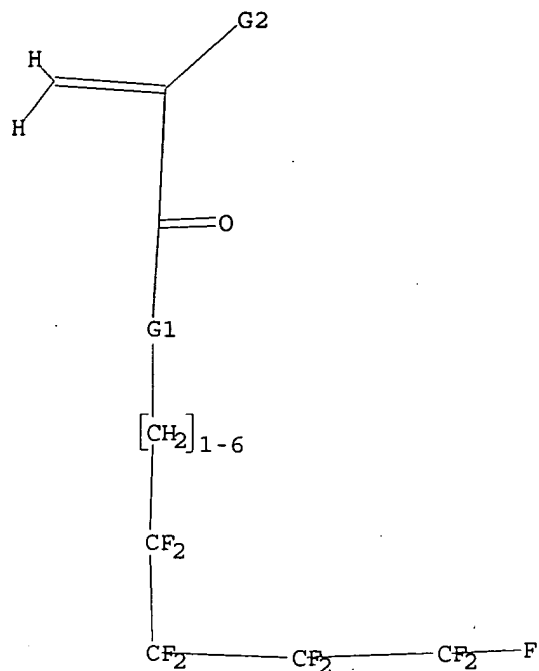
L11 QUE L10 AND L9

=> d

L11 HAS NO ANSWERS

L9 SCR 970 AND 2067

L10 STR



G1 O, S, N

G2 CH<sub>2</sub>, H

Structure attributes must be viewed using STN Express query preparation.

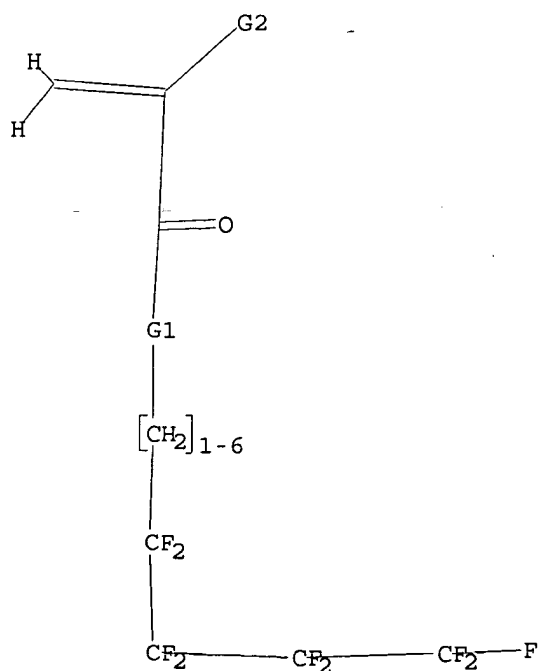
L11 QUE ABB=ON PLU=ON L10 AND L9

=> d

L11 HAS NO ANSWERS

L9 SCR 970 AND 2067

L10 STR



G1 O, S, N

G2 CH<sub>2</sub>, H

Structure attributes must be viewed using STN Express query preparation.

L11 QUE ABB=ON PLU=ON L10 AND L9

=> s l11 sss sam

SAMPLE SEARCH INITIATED 20:41:17 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 458 TO ITERATE

100.0% PROCESSED 458 ITERATIONS  
SEARCH TIME: 00.00.01

19 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 7877 TO 10443  
PROJECTED ANSWERS: 119 TO 641

L12 19 SEA SSS SAM L10 AND L9

=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 50 S L3 SSS SAM  
L5 SCREEN 970 AND 2067  
L6 STRUCTURE UPLOADED  
L7 QUE L6 AND L5  
L8 39 S L7 SSS SAM  
L9 SCREEN 970 AND 2067  
L10 STRUCTURE UPLOADED  
L11 QUE L10 AND L9  
L12 19 S L11 SSS SAM

=> s l4 or l8 or l12

L13 102 L4 OR L8 OR L12

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE

ENTRY

TOTAL

SESSION

FULL ESTIMATED COST

1.68

1.89

FILE 'HCAPLUS' ENTERED AT 20:41:37 ON 17 SEP 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

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FILE 'CAPLUS' ENTERED AT 20:41:37 ON 17 SEP 2004

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PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004

CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l13

L14 238 L13

=> duplicates remove l14

DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L14

L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)

=> s oxime sulfonate

L16 301 OXIME SULFONATE

=> s l16 and l14



L17 3 L16 AND L14

=> d 117 1-3 ibib hitstr

L17 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2004 ACS on STN

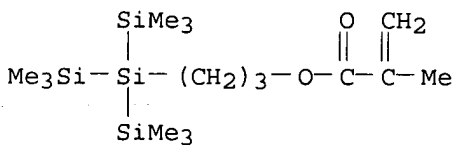
ACCESSION NUMBER: 2004:200910 HCAPLUS  
DOCUMENT NUMBER: 140:243596  
TITLE: Chemically amplified positive photoresists suppressing development defects  
INVENTOR(S): Momota, Atsushi  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004078105	A2	20040311	JP 2002-241946	20020822
US 2004048190	A1	20040311	US 2003-642576	20030819
PRIORITY APPLN. INFO.:			JP 2002-241946	A 20020822
OTHER SOURCE(S):	MARPAT	140:243596		

IT 668476-75-3P  
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)  
RN 668476-75-3 HCAPLUS  
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate,  $\alpha$ -(2-methyl-1-oxo-2-propenyl)- $\omega$ -methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

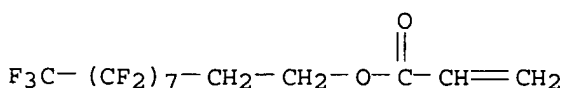
CM 1

CRN 114349-68-7  
CMF C16 H38 O2 Si4



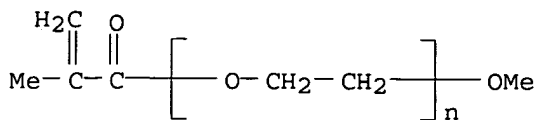
CM 2

CRN 27905-45-9  
CMF C13 H7 F17 O2



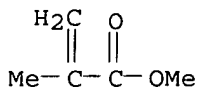
CM 3

CRN 26915-72-0  
CMF (C2 H4 O)<sub>n</sub> C5 H8 O2  
CCI PMS



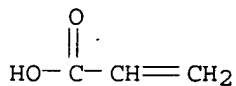
CM 4

CRN 80-62-6  
CMF C5 H8 O2



CM 5

CRN 79-10-7  
CMF C3 H4 O2



L17 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2004:200910 CAPLUS

DOCUMENT NUMBER: 140:243596

TITLE: Chemically amplified positive photoresists suppressing development defects

INVENTOR(S): Momota, Atsushi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004078105	A2	20040311	JP 2002-241946	20020822
US 2004048190	A1	20040311	US 2003-642576	20030819
PRIORITY APPLN. INFO.: OTHER SOURCE(S):			JP 2002-241946	A 20020822

IT 668476-75-3P

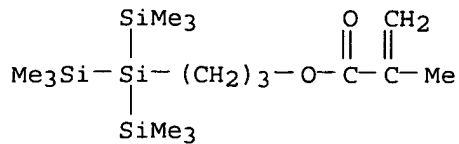
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

RN 668476-75-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate, α-(2-methyl-1-oxo-2-propenyl)-ω-methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

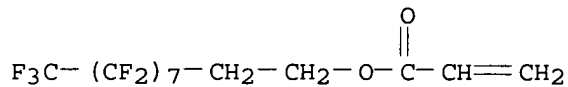
CRN 114349-68-7  
CMF C16 H38 O2 Si4



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

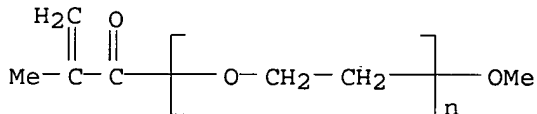


CM 3

CRN 26915-72-0

CMF (C2 H4 O)<sub>n</sub> C5 H8 O2

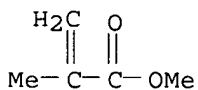
CCI PMS



CM 4

CRN 80-62-6

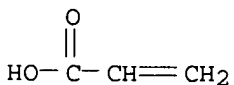
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



L17 ANSWER 3 OF 3 USPATFULL on STN

ACCESSION NUMBER: 2004:63672 USPATFULL

TITLE: Positive photoresist composition

INVENTOR(S): Momota, Makoto, Shizuoka, JAPAN

PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2004048190	A1	20040311

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2002-241946	20020822
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W., WASHINGTON, DC, 20037	
NUMBER OF CLAIMS:	8	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1349	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 668476-75-3P

(surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

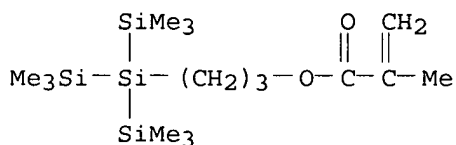
RN 668476-75-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with  
3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate,  
 $\alpha$ -(2-methyl-1-oxo-2-propenyl)- $\omega$ -methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 114349-68-7

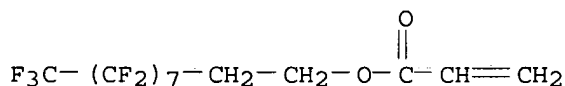
CMF C16 H38 O2 Si4



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

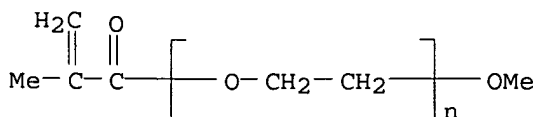


CM 3

CRN 26915-72-0

CMF (C2 H4 O)<sub>n</sub> C5 H8 O2

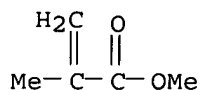
CCI PMS



CM 4

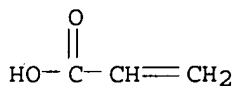
CRN 80-62-6

CMF C5 H8 O2



CM 5

CRN 79-10-7  
CMF C3 H4 O2



=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 50 S L3 SSS SAM  
L5 SCREEN 970 AND 2067  
L6 STRUCTURE UPLOADED  
L7 QUE L6 AND L5  
L8 39 S L7 SSS SAM  
L9 SCREEN 970 AND 2067  
L10 STRUCTURE UPLOADED  
L11 QUE L10 AND L9  
L12 19 S L11 SSS SAM  
L13 102 S L4 OR L8 OR L12

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004

L14 238 S L13  
L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)  
L16 301 S OXIME SULFONATE  
L17 3 S L16 AND L14

=> s l14 and (resist or photoresist)

L18 9 L14 AND (RESIST OR PHOTORESIST)

=> s l18 not l17

L19 6 L18 NOT L17

=> d l19 1-6 ibib hitstr

L19 ANSWER 1 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2003:735196 HCAPLUS

DOCUMENT NUMBER: 139:267983

TITLE: Positive-working **photoresist** composition  
containing polymer with fluoro-aliphatic group

INVENTOR(S): Fujimori, Toru

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

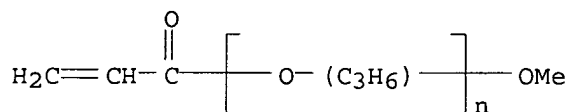
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

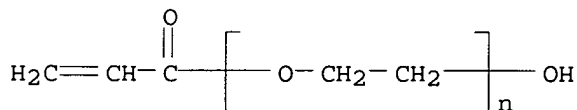
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	-----

JP 2003262952 A2 20030919 JP 2002-65444 20020311  
PRIORITY APPLN. INFO.: JP 2002-65444 20020311

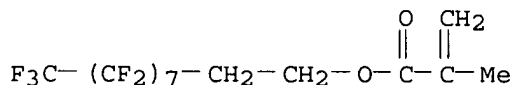
IT 602299-35-4  
RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)  
(surfactant; pos. **photoresist** composition containing polymer with fluoro-aliphatic group)  
RN 602299-35-4 HCAPLUS  
CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl ester, polymer with  $\alpha$ -(1-oxo-2-propenyl)- $\omega$ -hydroxypoly[oxy-1,2-ethanediyl] and  $\alpha$ -(1-oxo-2-propenyl)- $\omega$ -methoxypoly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)  
CM 1  
CRN 83844-54-6  
CMF (C3 H6 O)<sub>n</sub> C4 H6 O2  
CCI IDS, PMS



CM 2  
CRN 26403-58-7  
CMF (C2 H4 O)<sub>n</sub> C3 H4 O2  
CCI PMS



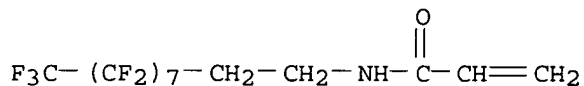
CM 3  
CRN 1996-88-9  
CMF C14 H9 F17 O2



L19 ANSWER 2 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN  
ACCESSION NUMBER: 1998:335551 HCAPLUS  
DOCUMENT NUMBER: 129:54119  
TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their (polymer) films, and **photoresists** using the same  
INVENTOR(S): Miyashita, Tokuji  
PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji  
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

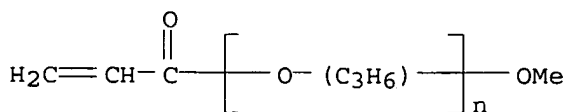
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 JP 10139747      A2      19980526      JP 1996-312953      19961108  
 PRIORITY APPLN. INFO.:      JP 1996-312953      19961108  
 OTHER SOURCE(S):      MARPAT 129:54119  
 IT      208589-71-3P  
 RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or  
 engineered material use); PREP (Preparation); USES (Uses)  
 (LB films of N-polyfluoroalkyl(meth)acrylamides and their polymers with  
 good water repellency, photosensitivity, and slip property)  
 RN      208589-71-3      HCAPLUS  
 CN      2-Propenamide, N-(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
 heptadecafluorodecyl)-, homopolymer (9CI)      (CA INDEX NAME)  
  
 CM      1  
  
 CRN      208589-64-4  
 CMF      C13 H8 F17 N O



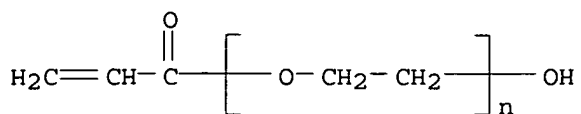
L19 ANSWER 3 OF 6      CAPLUS      COPYRIGHT 2004 ACS on STN  
 ACCESSION NUMBER:      2003:735196      CAPLUS  
 DOCUMENT NUMBER:      139:267983  
 TITLE:      Positive-working **photoresist** composition  
 containing polymer with fluoro-aliphatic group  
 INVENTOR(S):      Fujimori, Toru  
 PATENT ASSIGNEE(S):      Fuji Photo Film Co., Ltd., Japan  
 SOURCE:      Jpn. Kokai Tokkyo Koho, 88 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE:      Patent  
 LANGUAGE:      Japanese  
 FAMILY ACC. NUM. COUNT:      1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003262952	A2	20030919	JP 2002-65444	20020311
PRIORITY APPLN. INFO.:			JP 2002-65444	20020311

IT      602299-35-4  
 RL: MOA (Modifier or additive use); TEM (Technical or engineered material  
 use); USES (Uses)  
 (surfactant; pos. **photoresist** composition containing polymer with  
 fluoro-aliphatic group)  
 RN      602299-35-4      CAPLUS  
 CN      2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
 heptadecafluorodecyl ester, polymer with  $\alpha$ -(1-oxo-2-propenyl)-  
 $\omega$ -hydroxypoly(oxy-1,2-ethanediyl) and  $\alpha$ -(1-oxo-2-propenyl)-  
 $\omega$ -methoxypoly[oxy(methyl-1,2-ethanediyl)] (9CI)      (CA INDEX NAME)  
  
 CM      1  
  
 CRN      83844-54-6  
 CMF      (C3 H6 O)<sub>n</sub> C4 H6 O2  
 CCI      IDS, PMS

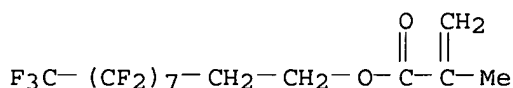


CRN 26403-58-7  
CMF (C2 H4 O)n C3 H4 O2  
CCI PMS



CM 3

CRN 1996-88-9  
CMF C14 H9 F17 O2



L19 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1998:335551 CAPLUS

DOCUMENT NUMBER: 129:54119

TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their  
(polymer) films, and **photoresists** using the  
same

INVENTOR(S): Miyashita, Tokuji

PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10139747	A2	19980526	JP 1996-312953	19961108
PRIORITY APPLN. INFO.:			JP 1996-312953	19961108
OTHER SOURCE(S):	MARPAT	129:54119		

IT 208589-71-3P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or  
engineered material use); PREP (Preparation); USES (Uses)

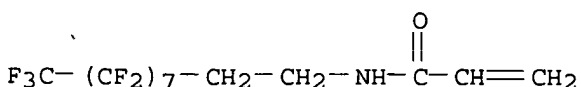
(LB films of N-polyfluoroalkyl(meth)acrylamides and their polymers with  
good water repellency, photosensitivity, and slip property)

RN 208589-71-3 CAPLUS

CN 2-Propenamide, N-(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 208589-64-4  
CMF C13 H8 F17 N O



L19 ANSWER 5 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:59638 USPATFULL

TITLE: Top coating for synthetic leathers



INVENTOR(S) : Huang, Hsu-Nan, Newark, DE, UNITED STATES

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002033468	A1	20020321
APPLICATION INFO.:	US 2001-970478	A1	20011004 (9)
RELATED APPLN. INFO.:	Division of Ser. No. US 2000-495132, filed on 31 Jan 2000, PENDING		

	NUMBER	DATE
PRIORITY INFORMATION:	US 1999-123601P	19990310 (60)
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	E I DU PONT DE NEMOURS AND COMPANY, LEGAL DEPARTMENT - PATENTS, 1007 MARKET STREET, WILMINGTON, DE, 19898	
NUMBER OF CLAIMS:	11	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1042	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 292849-59-3P		

(water- and oil-repellent coating compns. for synthetic grain leather)

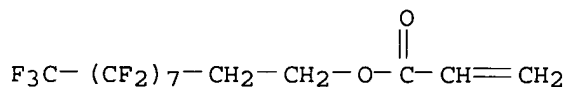
RN 292849-59-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate, N-(hydroxymethyl)-2-propenamide and  $\alpha$ -(2-methyl-1-oxo-2-propenyl)- $\omega$ -hydroxypoly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

CMF C13 H7 F17 O2

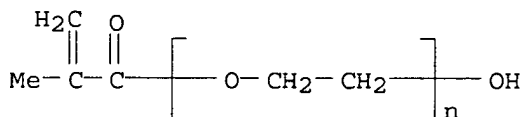


CM 2

CRN 25736-86-1

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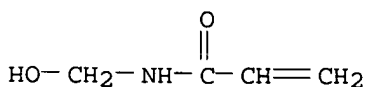
CCI PMS



CM 3

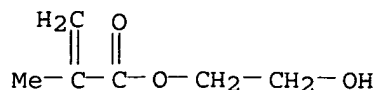
CRN 924-42-5

CMF C4 H7 N O2



CM 4

CRN 868-77-9



L19 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:45669 USPATFULL  
 TITLE: Top coating for synthetic leathers  
 INVENTOR(S): Huang, Hsu-Nan, Newark, DE, United States  
 PATENT ASSIGNEE(S): E. I. du Pont de Nemours and Company, Wilmington, DE, United States (U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6353051	B1	20020305
APPLICATION INFO.:	US 2000-495132		20000131 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	US 1999-123601P	19990310 (60)
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Yoon, Tae H.	
NUMBER OF CLAIMS:	9	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	1019	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 292849-59-3P

(water- and oil-repellent coating compns. for synthetic grain leather)

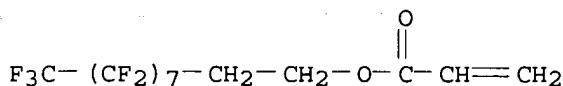
RN 292849-59-3 USPATFULL

CM 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with  
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate,  
 N-(hydroxymethyl)-2-propenamide and  $\alpha$ -(2-methyl-1-oxo-2-propenyl)-  
 $\omega$ -hydroxypoly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

CMF C13 H7 F17 O2

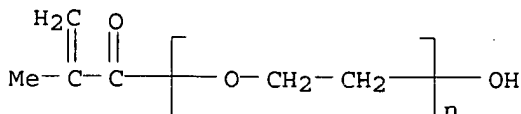


CM 2

CRN 25736-86-1

CMF (C2 H4 O)<sub>n</sub> C4 H6 O2

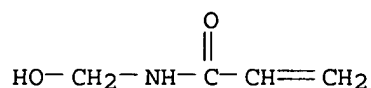
CCI PMS



CM 3

CRN 924-42-5

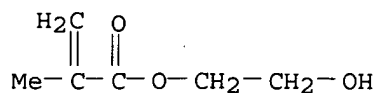
CMF C4 H7 N O2



CM 4

CRN 868-77-9

CMF C6 H10 O3



=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 50 S L3 SSS SAM  
L5 SCREEN 970 AND 2067  
L6 STRUCTURE UPLOADED  
L7 QUE L6 AND L5  
L8 39 S L7 SSS SAM  
L9 SCREEN 970 AND 2067  
L10 STRUCTURE UPLOADED  
L11 QUE L10 AND L9  
L12 19 S L11 SSS SAM  
L13 102 S L4 OR L8 OR L12

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004

L14 238 S L13  
L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)  
L16 301 S OXIME SULFONATE  
L17 3 S L16 AND L14  
L18 9 S L14 AND (RESIST OR PHOTORESIST)  
L19 6 S L18 NOT L17

=> exit y

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

52.86

54.75

STN INTERNATIONAL LOGOFF AT 20:45:24 ON 17 SEP 2004

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1752YXC

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

\* \* \* \* \* Welcome to STN International \* \* \* \* \*

NEWS 1 Web Page URLs for STN Seminar Schedule - N. America  
NEWS 2 "Ask CAS" for self-help around the clock  
NEWS 3 May 12 EXTEND option available in structure searching  
NEWS 4 May 12 Polymer links for the POLYLINK command completed in REGISTRY  
NEWS 5 May 27 New UPM (Update Code Maximum) field for more efficient patent  
SDIs in Caplus  
NEWS 6 May 27 Caplus super roles and document types searchable in REGISTRY  
NEWS 7 Jun 28 Additional enzyme-catalyzed reactions added to CASREACT  
NEWS 8 Jun 28 ANTE, AQUALINE, BIOENG, CIVILENG, ENVIROENG, MECHENG,  
and WATER from CSA now available on STN(R)  
NEWS 9 Jul 12 BEILSTEIN enhanced with new display and select options,  
resulting in a closer connection to BABS  
NEWS 10 Jul 30 BEILSTEIN on STN workshop to be held August 24 in conjunction  
with the 228th ACS National Meeting  
NEWS 11 AUG 02 IFIPAT/IFIUDB/IFICDB reloaded with new search and display  
fields  
NEWS 12 AUG 02 Caplus and CA patent records enhanced with European and Japan  
Patent Office Classifications  
NEWS 13 AUG 02 STN User Update to be held August 22 in conjunction with the  
228th ACS National Meeting  
NEWS 14 AUG 02 The Analysis Edition of STN Express with Discover!  
(Version 7.01 for Windows) now available  
NEWS 15 AUG 04 Pricing for the Save Answers for SciFinder Wizard within  
STN Express with Discover! will change September 1, 2004  
NEWS 16 AUG 27 BIOCOMMERCE: Changes and enhancements to content coverage  
NEWS 17 AUG 27 BIOTECHABS/BIOTECHDS: Two new display fields added for legal  
status data from INPADOC  
NEWS 18 SEP 01 INPADOC: New family current-awareness alert (SDI) available  
NEWS 19 SEP 01 New pricing for the Save Answers for SciFinder Wizard within  
STN Express with Discover!  
NEWS 20 SEP 01 New display format, HITSTR, available in WPIDS/WPINDEX/WPIX  
NEWS 21 SEP 14 STN Patent Forum to be held October 13, 2004, in Iselin, NJ  
  
NEWS EXPRESS JULY 30 CURRENT WINDOWS VERSION IS V7.01, CURRENT  
MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),  
AND CURRENT DISCOVER FILE IS DATED 11 AUGUST 2004  
NEWS HOURS STN Operating Hours Plus Help Desk Availability  
NEWS INTER General Internet Information  
NEWS LOGIN Welcome Banner and News Items  
NEWS PHONE Direct Dial and Telecommunication Network Access to STN  
NEWS WWW CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that  
specific topic.

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\* \* \* \* \* STN Columbus \* \* \* \* \*

FILE 'HOME' ENTERED AT 20:47:48 ON 17 SEP 2004

=> ....Testing the current file.... screen

THIS COMMAND NOT AVAILABLE IN THE CURRENT FILE

Please change to a suitable file and repeat your upload

Some commands only work in certain files. For example, the EXPAND  
command can only be used to look at the index in a file which has an  
index. Enter "HELP COMMANDS" at an arrow prompt (=>) for a list of  
commands which can be used in this file.

=> file reg		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'REGISTRY' ENTERED AT 20:48:21 ON 17 SEP 2004  
 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
 PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
 COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file  
 provided by InfoChem.

STRUCTURE FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5  
 DICTIONARY FILE UPDATES: 16 SEP 2004 HIGHEST RN 746205-18-5

TSCA INFORMATION NOW CURRENT THROUGH MAY 21, 2004

Please note that search-term pricing does apply when  
 conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more  
 information enter HELP PROP at an arrow prompt in the file or refer  
 to the file summary sheet on the web at:  
<http://www.cas.org/ONLINE/DBSS/registryss.html>

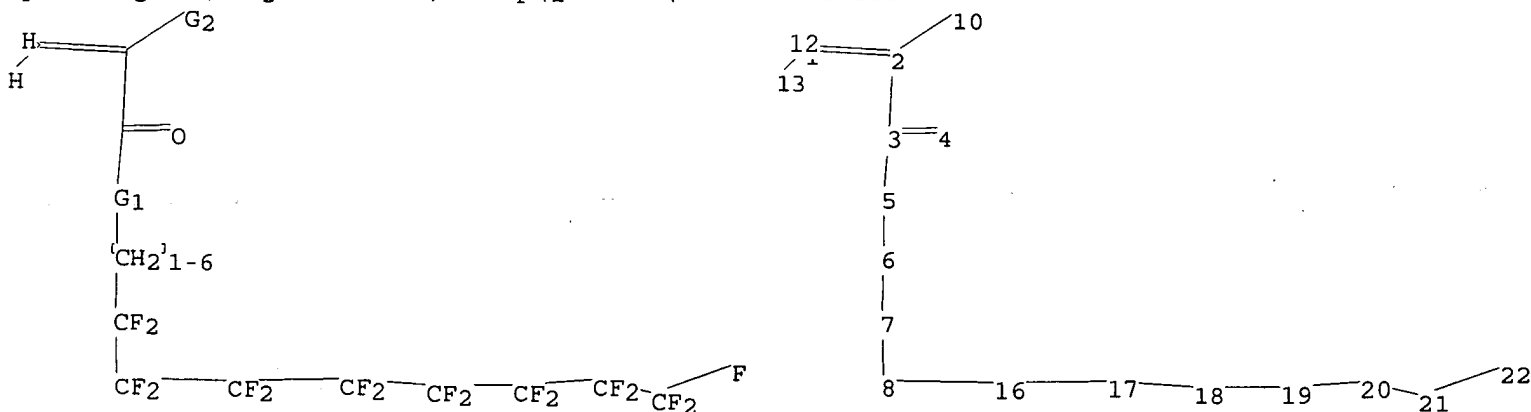
=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L1 SCREEN CREATED

=>  
 Uploading C:\Program Files\Stnexp\Queries\10642576-3.str



chain nodes :

1 2 3 4 5 6 7 8 10 12 13 16 17 18 19 20 21 22

chain bonds :

1-2 1-12 1-13 2-3 2-10 3-4 3-5 5-6 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21  
 21-22

exact/norm bonds :

2-10 3-4 3-5 5-6

exact bonds :

1-2 1-12 1-13 2-3 6-7 7-8 8-16 16-17 17-18 18-19 19-20 20-21 21-22

G1:O,S,N

G2:CH2,H

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 12:CLASS  
13:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS 21:CLASS 22:CLASS

L2 STRUCTURE UPLOADED

=> que L2 AND L1

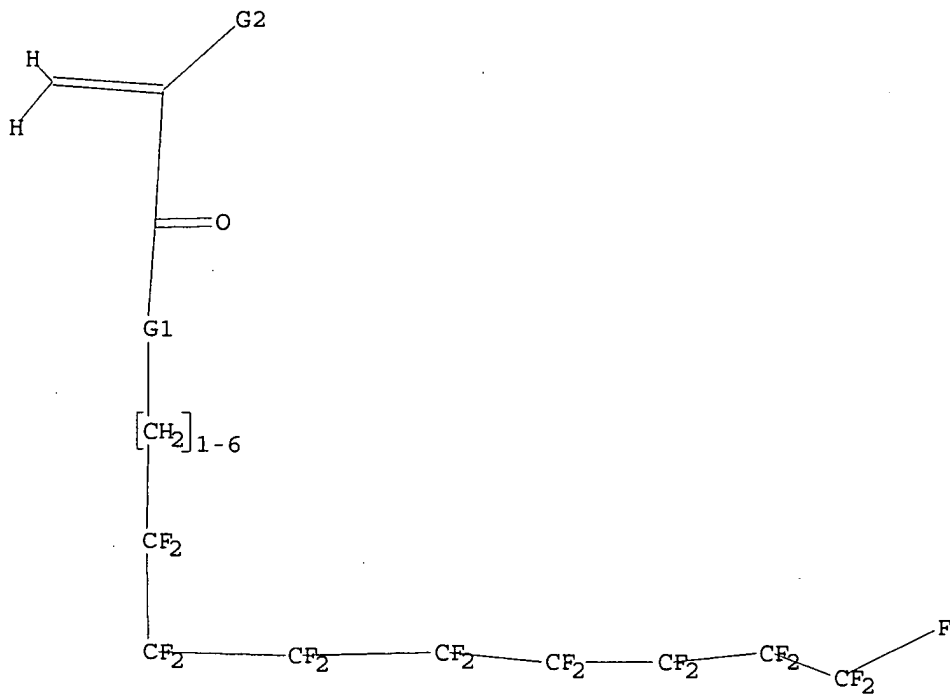
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 970 AND 2067

L2 STR



G1 O,S,N

G2 CH2,H

Structure attributes must be viewed using STN Express query preparation.

L3 QUE ABB=ON PLU=ON L2 AND L1

=> s 13

SAMPLE SEARCH INITIATED 20:48:59 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 350 TO ITERATE

100.0% PROCESSED 350 ITERATIONS

50 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 5878 TO 8122  
PROJECTED ANSWERS: 2990 TO 4648

L4 50 SEA SSS SAM L2 AND L1

=> FIL HCAPLUS, CAPLUS, USPATFULL  
COST IN U.S. DOLLARS

SINCE FILE ENTRY	TOTAL SESSION
0.42	0.63

FILE 'HCAPLUS' ENTERED AT 20:49:07 ON 17 SEP 2004  
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FILE 'CAPLUS' ENTERED AT 20:49:07 ON 17 SEP 2004  
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FILE 'USPATFULL' ENTERED AT 20:49:07 ON 17 SEP 2004  
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l4 and (oxime sulfonate)  
L5 3 L4 AND (OXIME SULFONATE)

=> d l5 1-3 ibib

L5 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2004:200910 HCAPLUS  
DOCUMENT NUMBER: 140:243596  
TITLE: Chemically amplified positive photoresists suppressing development defects  
INVENTOR(S): Momota, Atsushi  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004078105	A2	20040311	JP 2002-241946	20020822
US 2004048190	A1	20040311	US 2003-642576	20030819
PRIORITY APPLN. INFO.:			JP 2002-241946	A 20020822
OTHER SOURCE(S):	MARPAT 140:243596			

L5 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2004:200910 CAPLUS  
DOCUMENT NUMBER: 140:243596  
TITLE: Chemically amplified positive photoresists suppressing development defects  
INVENTOR(S): Momota, Atsushi  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004078105	A2	20040311	JP 2002-241946	20020822
US 2004048190	A1	20040311	US 2003-642576	20030819
PRIORITY APPLN. INFO.:			JP 2002-241946	A 20020822

OTHER SOURCE(S) : MARPAT 140:243596

L5 ANSWER 3 OF 3 USPATFULL on STN  
ACCESSION NUMBER: 2004:63672 USPATFULL  
TITLE: Positive photoresist composition  
INVENTOR(S) : Momota, Makoto, Shizuoka, JAPAN  
PATENT ASSIGNEE(S) : FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2004048190	A1	20040311
APPLICATION INFO.:	US 2003-642576	A1	20030819 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2002-241946	20020822
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W., WASHINGTON, DC, 20037	
NUMBER OF CLAIMS:	8	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1349	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> d his

(FILE 'HOME' ENTERED AT 20:47:48 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:48:21 ON 17 SEP 2004

L1 SCREEN 970 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 50 S L3

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:49:07 ON 17 SEP 2004  
L5 3 S L4 AND (OXIME SULFONATE)

=> s l4 and (resist or photoresist)  
L6 9 L4 AND (RESIST OR PHOTORESIST)

=> s l6 not l5  
L7 6 L6 NOT L5

=> d l7 1-6 cit

'CIT' IS NOT A VALID FORMAT

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L7 ANSWER 1 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN  
ACCESSION NUMBER: 2003:735196 HCAPLUS  
DOCUMENT NUMBER: 139:267983  
TITLE: Positive-working **photoresist** composition  
containing polymer with fluoro-aliphatic group  
INVENTOR(S): Fujimori, Toru  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003262952      A2      20030919      JP 2002-65444      20020311  
PRIORITY APPLN. INFO.:      JP 2002-65444      20020311

L7 ANSWER 2 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN  
ACCESSION NUMBER: 1998:335551 HCAPLUS  
DOCUMENT NUMBER: 129:54119  
TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their  
(polymer) films, and **photoresists** using the  
same  
INVENTOR(S): Miyashita, Tokuji  
PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji  
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10139747	A2	19980526	JP 1996-312953	19961108
PRIORITY APPLN. INFO.:			JP 1996-312953	19961108
OTHER SOURCE(S):	MARPAT	129:54119		

L7 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN  
ACCESSION NUMBER: 2003:735196 CAPLUS  
DOCUMENT NUMBER: 139:267983  
TITLE: Positive-working **photoresist** composition  
containing polymer with fluoro-aliphatic group  
INVENTOR(S): Fujimori, Toru  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003262952	A2	20030919	JP 2002-65444	20020311
PRIORITY APPLN. INFO.:			JP 2002-65444	20020311

L7 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN  
ACCESSION NUMBER: 1998:335551 CAPLUS  
DOCUMENT NUMBER: 129:54119  
TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their  
(polymer) films, and **photoresists** using the  
same  
INVENTOR(S): Miyashita, Tokuji  
PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji  
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10139747	A2	19980526	JP 1996-312953	19961108
PRIORITY APPLN. INFO.:			JP 1996-312953	19961108
OTHER SOURCE(S):	MARPAT	129:54119		

L7 ANSWER 5 OF 6 USPATFULL on STN  
ACCESSION NUMBER: 2002:59638 USPATFULL  
TITLE: Top coating for synthetic leathers  
INVENTOR(S): Huang, Hsu-Nan, Newark, DE, UNITED STATES

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002033468	A1	20020321
APPLICATION INFO.:	US 2001-970478	A1	20011004 (9)
RELATED APPLN. INFO.:	Division of Ser. No. US 2000-495132, filed on 31 Jan 2000, PENDING		

	NUMBER	DATE
PRIORITY INFORMATION:	US 1999-123601P	19990310 (60)
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	E I DU PONT DE NEMOURS AND COMPANY, LEGAL DEPARTMENT - PATENTS, 1007 MARKET STREET, WILMINGTON, DE, 19898	
NUMBER OF CLAIMS:	11	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1042	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:45669 USPATFULL

TITLE: Top coating for synthetic leathers

INVENTOR(S): Huang, Hsu-Nan, Newark, DE, United States

PATENT ASSIGNEE(S): E. I. du Pont de Nemours and Company, Wilmington, DE, United States (U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6353051	B1	20020305
APPLICATION INFO.:	US 2000-495132		20000131 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	US 1999-123601P	19990310 (60)
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Yoon, Tae H.	
NUMBER OF CLAIMS:	9	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	1019	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

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